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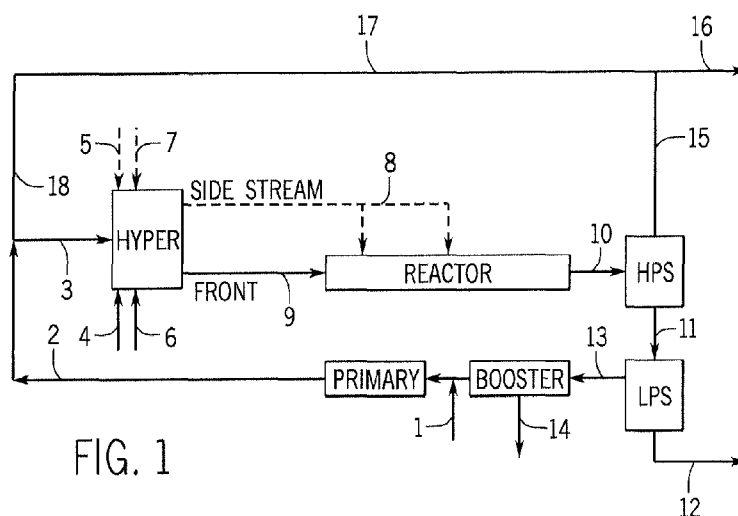
(54) **Title:** ETHYLENE-BASED POLYMERS FORMED USING ASYMMETRICAL POLYENES

FIG. 1

(57) **Abstract:** A composition comprising an ethylene-based polymer, the ethylene-based polymer having the following properties: a) at least one incorporated structure derived from a polyene selected from the group consisting of i) through x), as described herein; and b) a Mw(abs) versus I₂ relationship: Mw(abs) < A + B(I₂), wherein A = 2.40 × 10⁵ g/mole and B = -8.00 × 10³ (g/mole)/(dg/min). A composition comprising an ethylene-based polymer, the ethylene-based polymer comprising at least one incorporated structure derived from a polyene selected from the group consisting of i) through x), as described herein, wherein the polymer is formed in a reactor configuration comprising at least one tubular reactor.

